#### **Anti-Reflection Coatings**

Andrew Briggs
CHE 384T Lithography
10/26/2017

The University of Texas-Austin

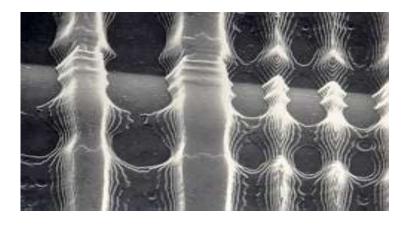
**Chemical Engineering** 

#### Outline

- Motivation
- Physics
- Modern Approaches

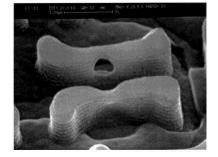
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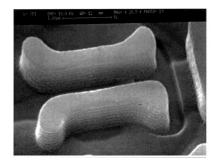
## Prize for the Ugliest SEM goes to:

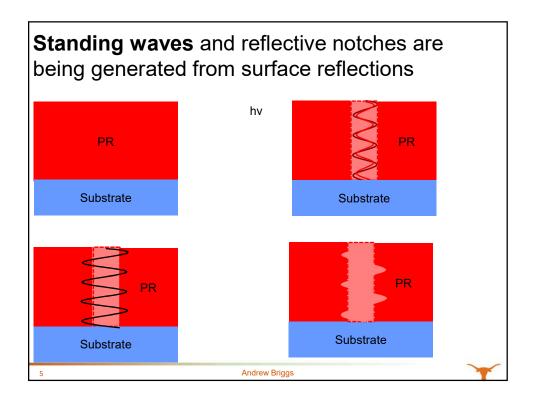


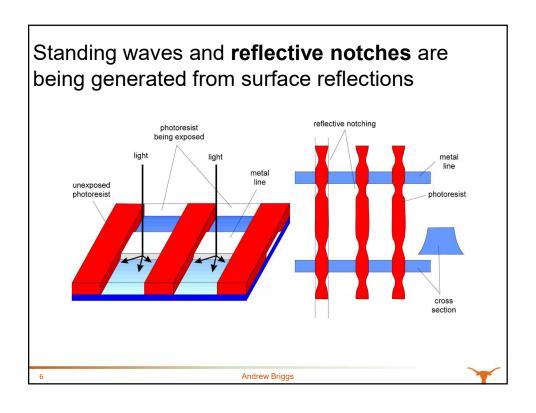
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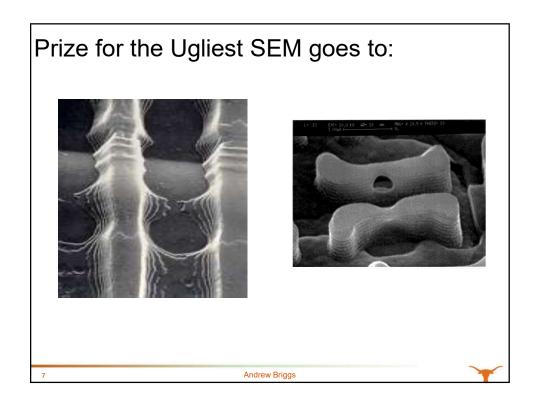
## Runner up?

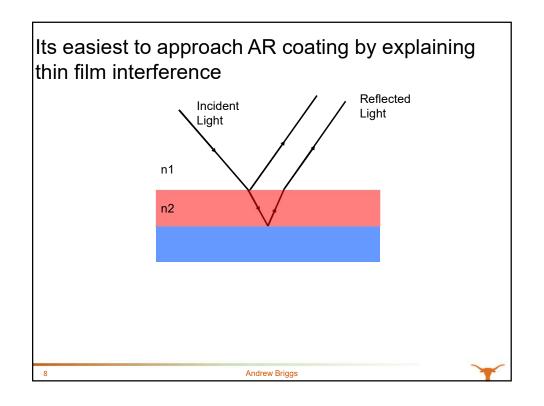


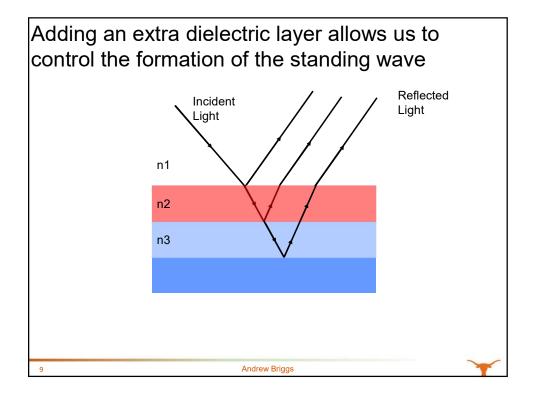


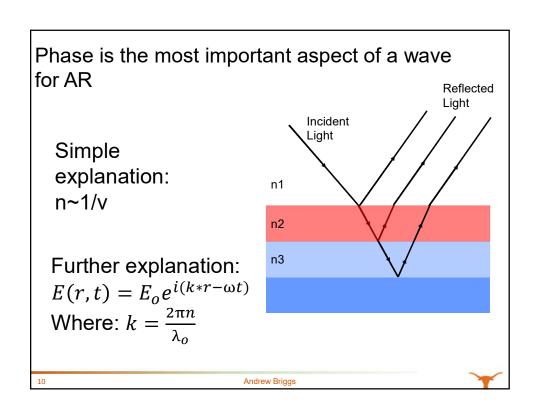


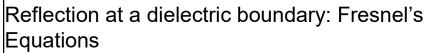


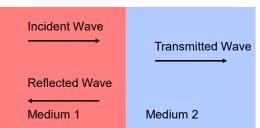












$$E_r = \left(\frac{n_1 - n_2}{n_1 + n_2}\right) E_i$$

$$E_t = \left(\frac{2n_1}{n_1 + n_2}\right) E_i$$

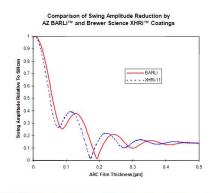
$$R = \left(\frac{n_1 - n_2}{n_1 + n_2}\right)^2$$

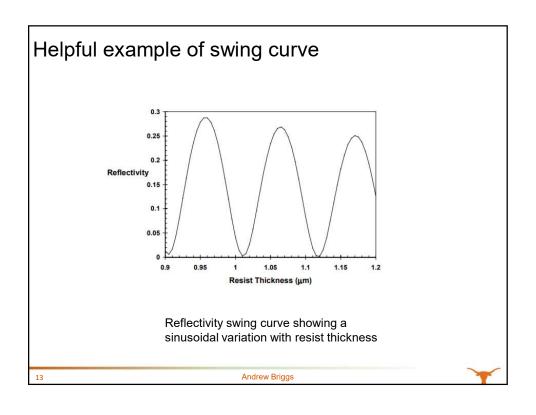
11

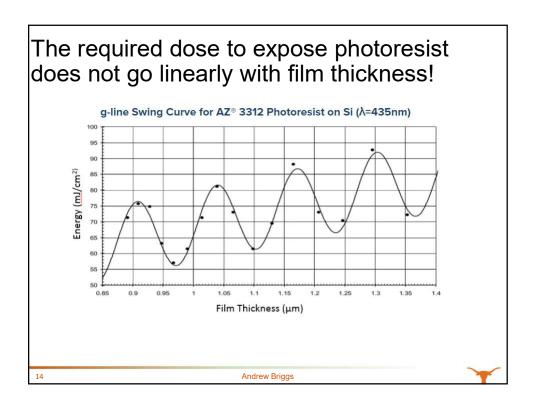
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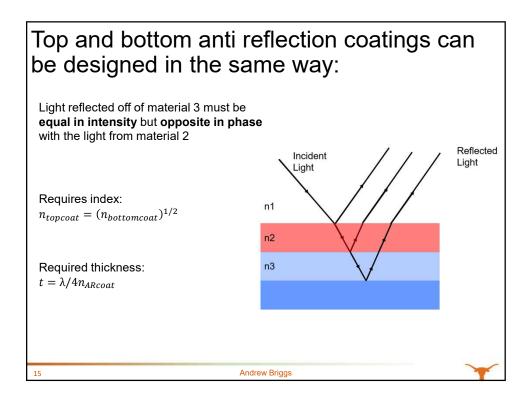
Swing curves are a fast way to compare AR coatings

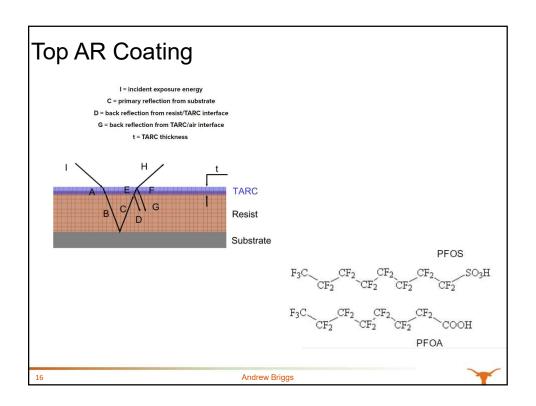
$$S = 4\sqrt{R_t R_b} e^{-\alpha_r d}$$

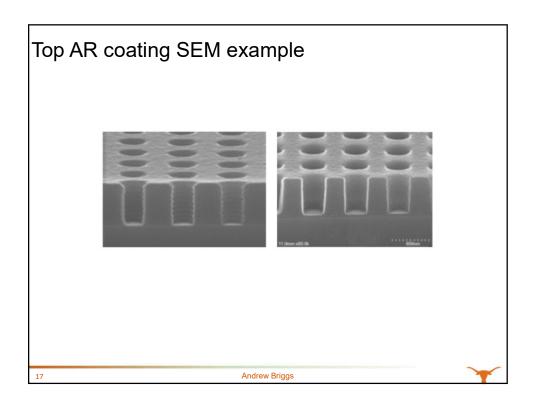


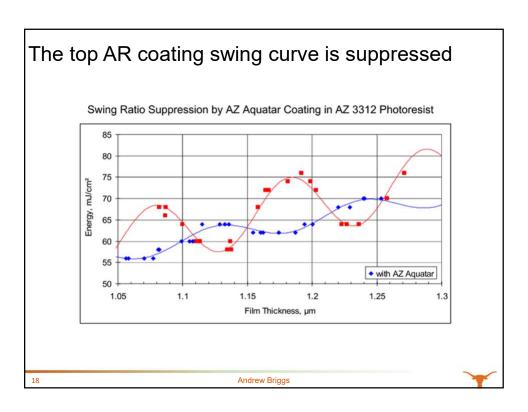


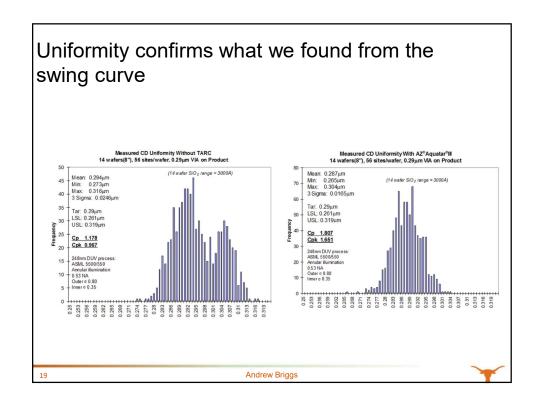


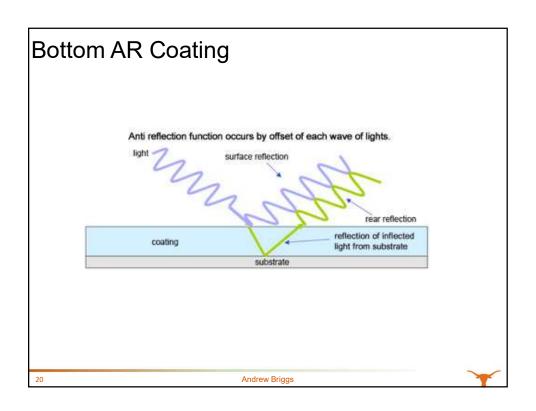




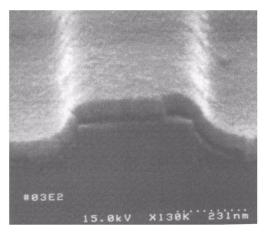






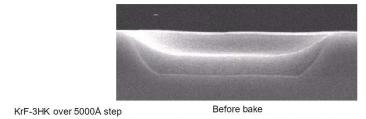


# Photoresists that are conformal lead to differing doses and reflections in each layer



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# Bottom anti-reflection coatings can be used to planarize a wafer



Baked at 190°C/60sec

